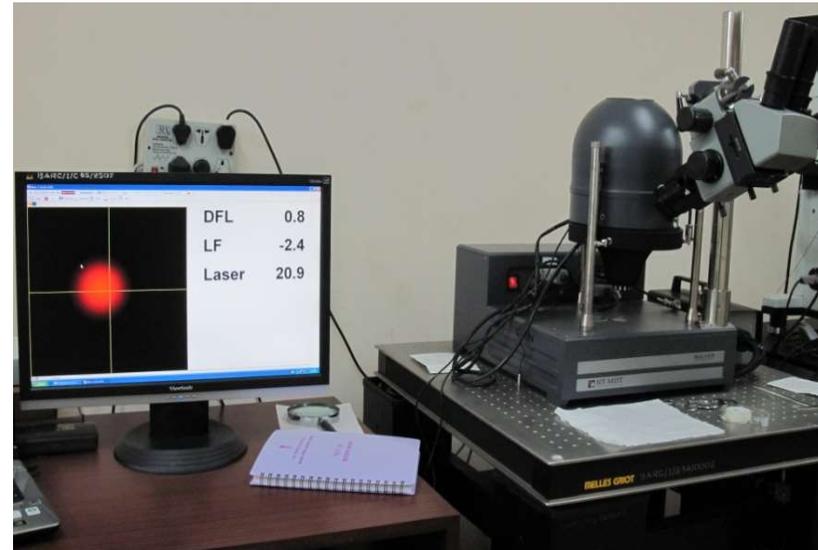


Thin film Characterization Facilities:

Atomic Force Microscopy:

(Model: P47H, NT-MDT, Russia)

Using this system, it is possible to carry out the measurement of surface morphology, quantification & scanning of elastic properties, Measurement of adhesion forces, force-distance spectroscopy between tip and sample surface, lateral force microscopy, phase imaging, scanning of magnetic domains etc., on thin films and surfaces.



UV-VIS-NIR Spectrophotometer:

(Make and Model: Shimadzu, UV-3101PC)

Transmission, reflection and diffused reflection measurements can be carried out in this spectrophotometer for solid, liquid and gas samples. This has been being utilized for characterization of multilayer devices & thin films and optical components. Wavelength Range: 190-3200 nm

